

Notice of References Cited

Application/Control No.

10/589,681

Applicant(s)/Patent Under
Reexamination
OGATA ET AL.

Examiner

PONDER N. THOMPSON

Art Unit

1795

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*	B	US-2002/0099147	07-2002	Yoshida et al.	525/329.7
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.